



SEC.760

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of:

Seung-pil Chung et al.

Group Art Unit: 1763

Serial No.: 09/689,814

Examiner: L. Alejandro Mulero

Filed: 13 October 2000

**METHOD FOR REMOVING OXIDE
LAYER AND SEMICONDUCTOR
MANUFACTURING APPARATUS
FOR REMOVING OXIDE LAYER**

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10/8/02
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AMENDMENT

Honorable Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Office Action dated 19 June 2002, the period for response to
which has been extended to 19 October 2002 by the petition enclosed herewith,
please amend the above-identified patent application as follows:

IN THE SPECIFICATION:

Please replace the paragraph beginning at page 13, line 22, with the following
rewritten paragraph:

-- In the state where the vertically movable susceptor 12 is placed at the lower
portion of the vacuum chamber 10, the silicon wafer 14 is loaded onto the susceptor
12. In order to create a vacuum condition in the vacuum chamber 10, the air or gases

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